

#5/Amnt A
4-17-02 JLD

I hereby certify that this correspondence is being deposited by FACSIMILE to the Commissioner of Patents and Trademarks, Washington, DC on April 15, 2002 by Colleen Dew.

Colleen J. Dew

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Group Art Unit 2822

In re application of : April 15, 2002
Axel Brintzinger et al. : Examiner: Monica Lewis
Serial No. : 09/873,537 :
Filed: June 4, 2001 : IBM Corporation
Title: DUAL DAMASCENE ANTI-FUSE : Dept. 18G/Bldg, 300-482
WITH VIA BEFORE WIRE : 2070 Route 52
Hopewell Junction, NY
12533-6531

Amendment

Commissioner for Patents and Trademarks
Washington, D.C. 20231

Sir:

Kindly amend the claims as follows:

- ALC
CWD
- 1 22. (amended) An interconnect structure in which an anti-fuse dielectric is
2 formed therein comprising:
3 a substrate having a first level of electrically conductive features;
4 a patterned anti-fuse dielectric layer formed on said substrate, wherein
5 said patterned anti-fuse dielectric layer includes an opening to at least one
6 of said first level of electrically conductive features;